FORM PTO-1449 (MODIFIED)			ATTY DOCKET NO.	SEF	SERIAL NO.				
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT			67,200-377	F	Filed Herewith				
			APPLICANT Fu-Liang Yang						
(Use several sheets if necessary)			FILING DATE Filed Herewith	GR	GROUP Unknown				
REFERENCE DESIGNATION U.S. PATENT DOCUMENTS									
EXAMINER	DOCUMENT			A	SUB	FILING			

REFERENCE DI	ESIGNAT	ION U.S. F	PATENT DOCUM	IENTS			
EXAMINER INITIAL		DOCUMENT NO.	DATE	NAME	CLASS	SUB CLASS	FILING DATE
OF	AA	5,023,671	Jun/1991	DiVincenzo et al		→	
of	AB	5,119,151	Jun/1992	Onda			
	AC						
	AD						
	ΑE						
	AF						
	AG						
	АН						
	ΑI						
	AJ					<u> </u>	

FOREIGN PATENT DOCUMENTS TRANSLATION SUB **EXAMINER** DOCUMENT YES/NO **CLASS** INITIAL COUNTRY **CLASS** NO. DATE ΑK ALAM AN

OTHER ART (including Author, Title, Date, pertinent pages, etc.)

AO Sallagoity et al, "Analysis of Width Edge Effects in Advanced Isolation Schemes for Deep Submicron CMOS Technologies", IEEE Trans. on Electron Devices, 44(11), Nov. 1996, pp. 1900-05.

AP Matsuda et al, "Novel Corner Rounding Process for Shallow Trench Isolation Utilizing MSTS (Micro-Structure Transformation of silicon). IEEE IEDM98, pp. 137-40.

EXAMINER DATE CONSIDERED 8/20/cs

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to application.